1. Title:	LPP Source Development for HVM EUV Lithography
2. Full names of all authors:	Björn A.M. Hansson, Igor V. Fomenkov, Norbert R. Böwering, Alex I. Ershov, William N. Partlo, David W. Myers, Alexander N. Bykanov, Oleh V. Khodykin, Jerzy R. Hoffman, Ernesto Vargas, Juan A. Chavez, Rodney D. Simmons, Georgiy O. Vaschenko, David C. Brandt

3. Abstract body:

This presentation provides a review of development results for a laser-produced-plasma (LPP) extreme-ultra-violet (EUV) source with performance targeted to meet joint requirements from all leading scanner manufacturers. We present the latest results on drive laser power and efficiency, source fuel, conversion efficiency, debris mitigation techniques, multi-layer-mirror coatings, collector efficiency, intermediate-focus (IF) metrology, mass-limited droplet generation, laser-to-droplet targeting control, and system use and experience. Results from several full-scale prototype systems will be presented. In addition, a multitude of smaller lab-scale experimental systems have also been constructed and tested. This presentation reviews the latest experimental results obtained on these systems with a focus on the topics most critical for an HVM source.